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A B S T R A C T

AN ION IMPLANTER OPERATING IN PULSED PLASMA MODE

5 The present invention relates to an ion implanter
IMP comprising a pulsed plasma source SPL, a substrate-
carrier tray PPS, and a power supply ALT for the tray.
The implanter also includes a capacitor C connected
directly to ground E and connected downstream from the
10 tray power supply ALT. The invention also provides a
method of using the implanter.

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35 Translation of the title and the abstract as they were when originally filed by the
Applicant. No account has been taken of any changes that may have been made
subsequently by the PCT Authorities acting ex officio, e.g. under PCT Rules 37.2,
38.2, and/or 48.3.